

Title (en)

FOCUSSED SUBSTRATE ALTERATION.

Title (de)

FOKUSSIERTER ALTERNIERUNG EINES SUBSTRATS.

Title (fr)

ALTERATION FOCALISEE D'UN SUBSTRAT.

Publication

EP 0198907 A1 19861029 (EN)

Application

EP 85905574 A 19851025

Priority

- US 66525184 A 19841026
- US 76937085 A 19850826

Abstract (en)

[origin: WO8602774A1] Alteration of a precisely located site on a substrate (35) using apparatus that comprises: a) a focusable ion source (10); b) a lens (22) positioned to focus ions emitted by the source into an ion beam (124); c) a vacuum chamber (30) for containing the substrate site in the path of the ion beam; and d) a directed gas inlet (55) positioned to provide a localized supply of a substance at the site whereby the beam interacts with the substances to cause the alteration localized at the site. Methods of performing the alteration are also disclosed.

Abstract (fr)

On altère avec exactitude un site précisément localisé sur un substrat (35) en balayant le site avec un faisceau focalisé d'ions (24) en présence d'un gaz (hydrocarbure ou hydrogène) au niveau du site pour former un dépôt opaque sur celui-ci.

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IPC 8 full level

G03F 1/00 (2012.01); **H01J 37/317** (2006.01)

CPC (source: EP)

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